

Synopsis V1.0
SEE Test Report for the Samsung DDR DRAM

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I. Introduction

This study was undertaken to determine the susceptibility of the Samsung KH41G0X38 1 Gbit DDR DRAM to destructive and nondestructive single-event effects (SEE). The device was monitored for SEUs, functional interrupts and destructive events induced by exposing it to a heavy ion beam at Michigan State University's SEE Test Facility.

II. Devices Tested

We tested a single Samsung KH41G0X38 DRAMs marked with date code 546. Note that with commercial devices, the same lot date code is no guarantee that the devices are from the same wafer diffusion lot or even from the same fabrication facility. However, we believe that since these devices are fabricated in the still relatively rare 90 nm feature-size technology and were supplied by the manufacturer that their provenance is traceable.

The device technology is 90 nm minimum feature size CMOS Double-Data-Rate Synchronous Dynamic Random Access Memory.

III. Test Facility

Facility: SEETF at the National Superconducting Cyclotron Facility, Michigan State University

Flux: (5×10^2 to 1×10^5 particles/cm²/s).

Fluence: All tests were run to (1×10^6 p/cm²) or until destructive or functional events occurred.

Table I: Ions/Energies and LET for this test

Ion/Energy per AMU	Approx. LET on die (MeV•cm ² /mg)
Xe/105	25
Xe/69.8	40

IV. Test Conditions

Test Temperature: Room Temperature for SEU, 85°C

Operating Frequency: (0-10 MHz).

Power Supply Voltage: (2.5V for both SEL SEU).

V. Test Methods

Because of the mode of operation of DRAM, all testing was performed dynamically at a clock speed of 100 MHz (DDR speed of 200 MHz) and with a checkerboard pattern (AA).

The Block diagram for control of the DUT is shown in Figure 1. The FPGA based controller interfaces to the FLASH daughter card and to a laptop, allowing control of the FPGA and uploading of new FPGA configurations and instructions for control of the DUT. Power for the DUT is supplied by means of a computer-controlled power supply. The National Instruments Labview interface monitors the power supply for overcurrent conditions and shuts down power to the DUT if such conditions are detected.

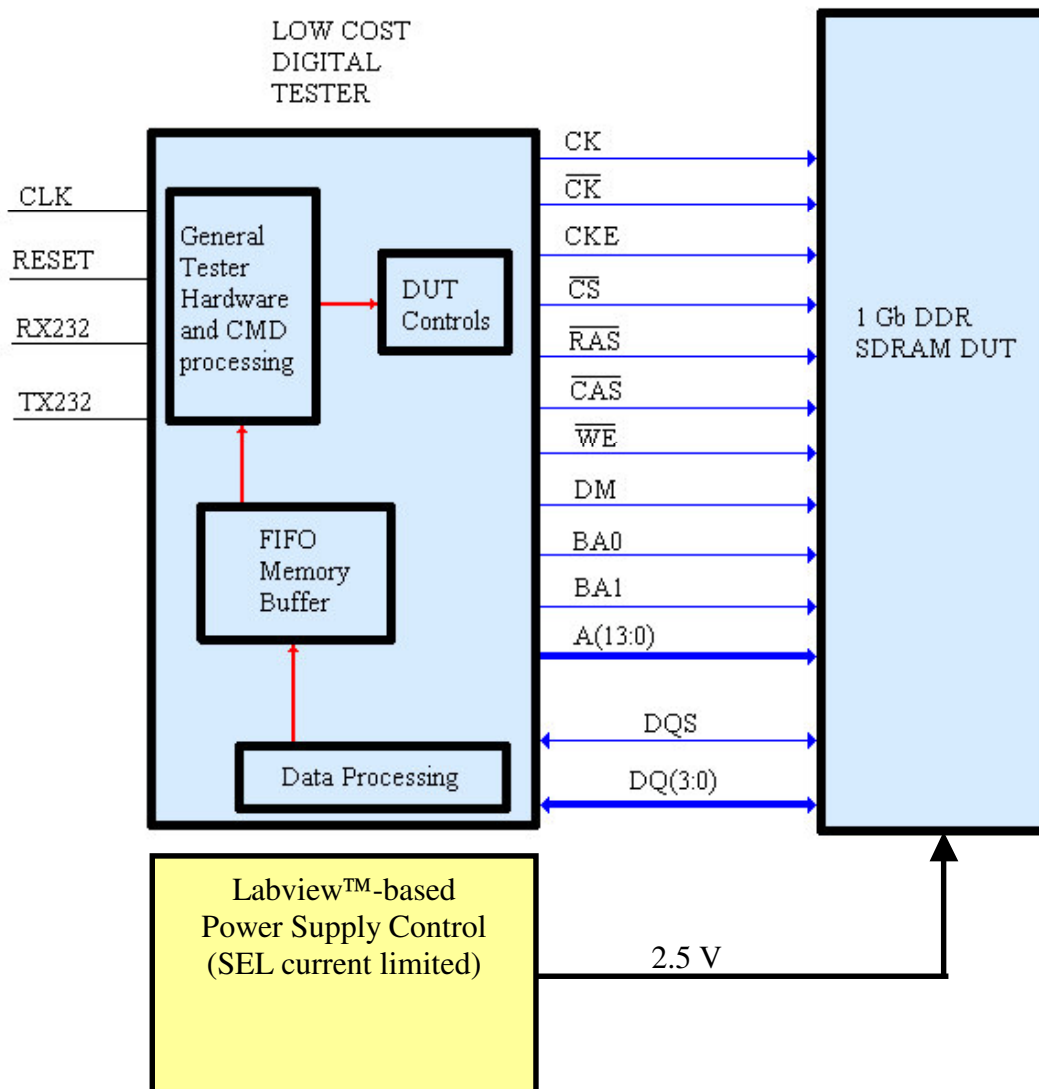


Figure 1. Overall Block Diagram for the testing SDRAMs with the low-cost tester.

VI. Results

During testing, the KH41G0X38 was irradiated with a single ion, Xenon, but at multiple angles to provide a greater range of incident effective LETs. The DUT was oriented normal to the incident beam, and at 45 and 60 degrees to the normal to yield higher effective LETs (~ 29 - $60 \text{ MeV}\cdot\text{cm}^2/\text{mg}$). SEUs, MBUs and SEFIs were seen for all LETs. SEL was seen only at the highest LET ($\sim 60 \text{ MeV}\cdot\text{cm}^2/\text{mg}$) and with the part heated to 85 degrees C. (Figure 2 shows the SEL cross section at $\text{LET}\sim 60 \text{ MeV}\cdot\text{cm}^2/\text{mg}$ and temperature 85 °C, along with upper limits for $\text{LET}\sim 36 \text{ MeV}\cdot\text{cm}^2/\text{mg}$.) No SEL was seen at room temperature up to an effective $\text{LET}\sim 60 \text{ MeV}\cdot\text{cm}^2/\text{mg}$. The SEFI cross section was near saturation over the range of LETs available for this test, while the SEU and MBU cross sections did not saturate. The relatively large SEFI cross section made it difficult to determine SEU cross sections or to pinpoint the fluence where a SEFI occurred. As such, SEFI and SEU and multi-bit upset (MBU) cross sections had to be determined during post-processing of the data. Figure 3 shows the SEU, MBU and SEFI cross sections

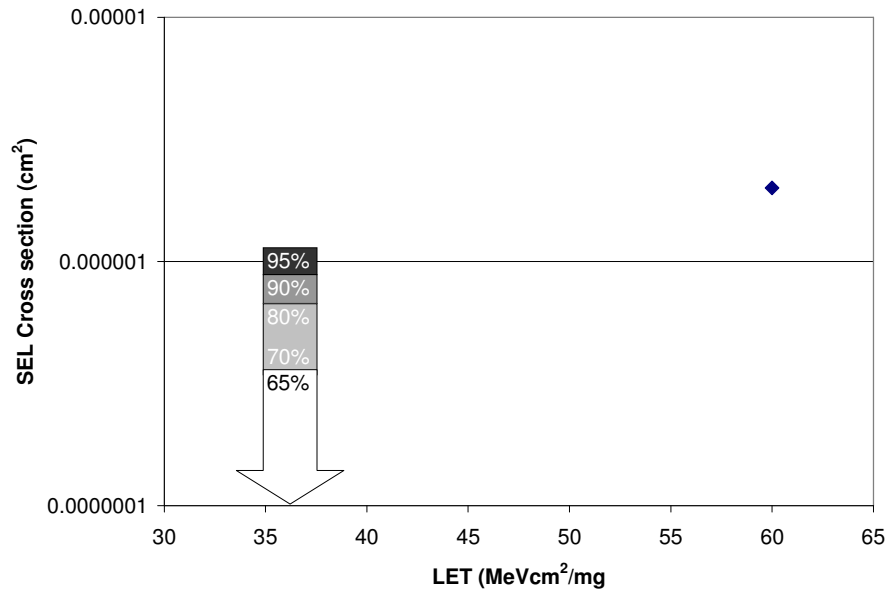


Figure 2 SEL cross section vs. LET (arrow at $\text{LET}=36$ indicates SEL was not observed and indicates the upper limits consistent with the given confidence limits).

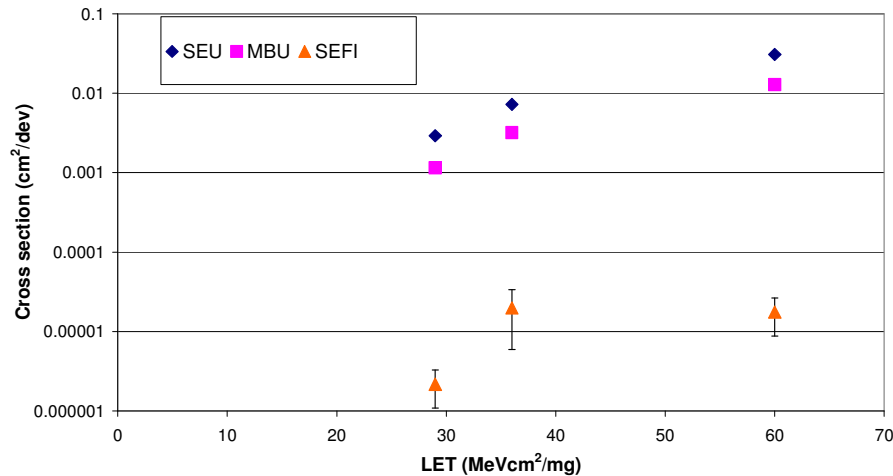


Figure 3 SEFI cross section vs. LET

No obvious incidence of stuck bits was seen either during the run or during post processing.

In looking at figure 3, several features are noteworthy. First, the SEU and MBU cross sections do not saturate at the highest effective LETs in the test, indicating that charge collection by diffusion plays a significant role in these parts for these phenomena. In contrast, the SEFI cross section seems to be saturating. A second point is that the MBU cross section is roughly 50% of the SEU cross section for all LETs used in this test. This may be because the ultra-high energy ion beam tends to create a sufficiently large charge track that angle effects are obscured. This also means that a hamming code would not be effective for these parts, although a modified hamming code (single nibble correct) or Reed-Solomon type code could be.

VII. Recommendations

In general, devices are categorized based on heavy ion test data into one of the four following categories:

- Category 1: Recommended for usage in all NASA/GSFC spaceflight applications.
 - Category 2: Recommended for usage in NASA/GSFC spaceflight applications, but may require mitigation techniques.
 - Category 3: Recommended for usage in some NASA/GSFC spaceflight applications, but requires extensive mitigation techniques or hard failure recovery mode.
 - Category 4: Not recommended for usage in any NASA/GSFC spaceflight applications.
- Research Test Vehicle: Please contact the P.I. before utilizing this device for spaceflight applications

The Samsung KH41G0X38 2 Gbit NAND Flash memory is a Category 3 device.

VIII. Further Test Requirements

This test represents a preliminary characterization of SEE vulnerability of the Samsung KH41G0X38. Additional testing is required before these devices can be considered for space applications. A minimum qualification involves determination of threshold and cross section vs. LET curves for all of the vulnerabilities identified in this test. Such a test should involve irradiation with multiple ions and multiple LETs. Since high-energy heavy-ion irradiation facilities do not exist with such capabilities, this characterization will have to take place at a lower-energy facility and will require modification of the part (e.g. by repackaging or thinning of the die for backside irradiation) so that the die can be exposed directly to the ion beam. In particular, testing at low LET and with protons is needed to more fully understand the extent of vulnerability to SEUs and SEFIs.

TID testing will be carried out to determine sensitivity to this degradation mode.

Appendix 1: